

Applicants: Choi et al. PATENT APPLICATION
Serial No: Unassigned Group Art Unit: Unassigned
Filed: Herewith Examiner: Unassigned
For: A METHOD OF MANUFACTURING A VACUUM CHUCK USED IN
IMPRINT LITHOGRAPHY

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Before calculation of the fees due, please preliminarily amend the application as follows:

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IN THE TITLE:

Please cancel "HIGH PRECISION ORIENTATION ALIGNMENT AND GAP
CONTROL STAGES FOR IMPRINT LITHOGRAPHY PROCESSES" and
replace with "A METHOD OF MANUFACTURING A VACUUM CHUCK USED
IN IMPRINT LITHOGRAPHY".

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IN THE DRAWINGS:

Applicant proposes to amend Figs. 4, 6B, and 11B of the patent application to harmonize with the description of the invention in the written Specification. To that end, a separate letter to the Chief Draftsperson is attached requesting that the Drawings be corrected.

Fig. 4 has been amended to include elements 110 and 114 as indicated on the accompanying drawings.

Fig. 6B has been amended to include elements 210 and to show frame 130 and re-label the same as element 206 as indicated on the accompanying drawings.

Fig. 11B has been amended to show wall shape 462 and re-label the same as element 464 and to show smooth curved cross section 462 and re-label the same as element 466 as indicated on the accompanying drawings.

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